5th EUV-FEL Workshop



Report of Contributions

Contribution ID: 1 Type: not specified

Opening remarks

Friday, 22 January 2021 12:30 (10 minutes)

Presenter: SUNAO ISHIHARA(REPRESENTATIVE OF EUV-FEL LIGHT SOURCE STUDY GROUP FOR INDUSTRIALIZATION)

Contribution ID: 2 Type: not specified

Fundamental Research to Solve the EUV Technical Issues, and Future Prospect for EUVL toward Advanced Devices Fabrication

Friday, 22 January 2021 12:40 (40 minutes)

Presenter: TAKEO WATANABE(CENTER FOR EUVL, DIRECTOR, LABORATORY OF ADVANCED SCIENCE AND TECHNOLOGY FOR INDUSTRY, DEAN, UNIVERSITY OF HYOGO)

Contribution ID: 3 Type: not specified

Compact Storage Ring FEL: a kW-scale EUV lithography source

Friday, 22 January 2021 13:20 (30 minutes)

Presenter: ROD LOEWEN(LYNCEAN TECHNOLOGIES, INC., (CTO))

Contribution ID: 4 Type: **not specified**

Construction and commissioning of cERL IR-FEL toward realization of the EUV-FEL

Friday, 22 January 2021 13:50 (30 minutes)

Presenter: NORIO NAKAMURA(KEK)

Contribution ID: 5 Type: **not specified**

Industrial application of accelerator : Medical RI production

Friday, 22 January 2021 14:20 (30 minutes)

Presenter: KENTARO HARADA(KEK)

Contribution ID: 6 Type: not specified

Driving Moore's Law through Process and Packaging Innovations

Friday, 22 January 2021 15:20 (30 minutes)

Presenter: NAOKI KITANO(INTEL K.K.)

Contribution ID: 7 Type: **not specified**

EUV Lithography as key scaling enabler for logic and memory

Friday, 22 January 2021 15:50 (30 minutes)

Presenter: GEERT VANDENBERGHE(IMEC)

Contribution ID: 8 Type: not specified

High-NA EUV Lithography exposure tool for EUV roadmap extension

Friday, 22 January 2021 16:20 (30 minutes)

Presenter: JAN VAN SCHOOT ET AL.(ASML)

Contribution ID: 9 Type: **not specified**

Closing address & photo-session

Friday, 22 January 2021 16:50 (10 minutes)

Presenter: HIROSHI KAWATA(KEK)